

L Number	Hits	Search Text	DB	Time stamp
1	57	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 07:30
2	2	((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2)) same (substrate near glass)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 07:32
3	11	((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2)) and (substrate same glass)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 07:59
4	9	(((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))) and (substrate same glass)) not (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2)) same (substrate near glass))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 07:32
5	37	((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2)) and (glass)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 07:59
6	26	(((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))) and (glass)) not (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))) same (substrate near glass)) (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2)) and (substrate same glass)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 08:08
7	32	((crosslinked cured (cross near linked)) same (polydimethylsiloxane dimethylpolysiloxane) same ((silicon near (dioxide oxide)) siO siO2 siO?sub.2) same (layer coating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 08:10
8	13	((crosslinked cured (cross near linked)) same (polydimethylsiloxane dimethylpolysiloxane) same ((silicon near (dioxide oxide)) siO siO2 siO?sub.2) same (layer coating)) not (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2)) same (substrate near glass)) "35")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 08:10
9	30	((crosslinked cured (cross near linked)) same (polydimethylsiloxane dimethylpolysiloxane) same ((silicon near (dioxide oxide)) siO siO2 siO?sub.2) same (layer coating)) not (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2)) same (substrate near glass)) (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))) and (substrate same glass)) (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2)) and (glass)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 08:10

10	20	<p>((((crosslinked cured (cross near linked)) same (polydimethylsiloxane dimethylpolysiloxane)) same ((silicon near (dioxide oxide)) siO siO2 siO?sub.2) same (layer coating)) not (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))) same (substrate near glass)) (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))) and (substrate same glass)) (((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas))) same (dimethyldichlorosilane me2sicl2 (me?sub.2 near sicl?sub.2) (ch?sub.3 near ?sub.2 near sicl?sub.2))) and ((glass)))) and glass</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/21 08:10
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